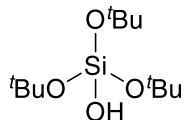


Catalog # 14-7015 Tri-t-butoxysilanol (99.999%-Si) PURATREM
is also valid for 98-6025



Thermal Behavior:

- Melting point 63-65°C [1], 65-66°C [1]
- Boiling point: 95°C/20 Torr
- Vapor pressure: ~20 Torr/115°C [5]

Technical Notes:

1. Precursor used for thin silicate film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
HfSi _x O _y	CVD	Tetradecane sol.	1 Torr	Hf(NMe ₂) ₄ ; H ₂ O	250-350°C	2
	ALD	85°C	0.68 Torr	Hf(NMeEt) ₄	210-375°C	3
	ALD	35°C	2 Torr	Hf(NO ₃) ₄	120°C, 160°C	4
AlSi _x O _y	ALD	115°C	-	AlMe ₃	200-300°C	5
	ALD	32-35°C	7.5 Torr	AlCl ₃ ; AlMe ₃ ; H ₂ O	150-500°C	6
SiO ₂	ALD	65-95°C	0.3 Torr	CatAlMe ₃	150-275°C	7
ZrSi _x O _y	ALD	35°C	0.3-0.4 Torr	Zr(NO ₃) ₄	162°C	8
TaSi _x O _y	ALD	-	0.15 Torr	Ta(OEt) ₅ ; H ₂ O	250°C	9

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